

## **Supporting Information**

### **Perovskite light-emitting devices with metal-insulator- semiconductor structure and carrier tunnelling**

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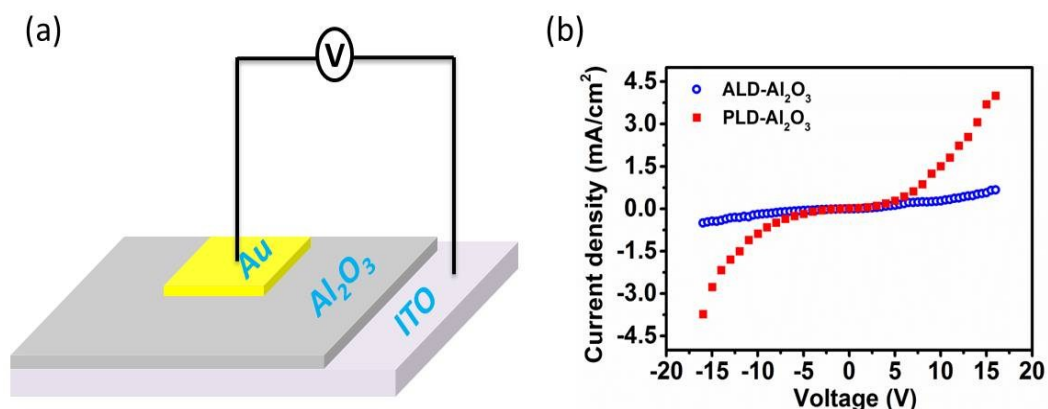


Figure S1. (a) Schematic structure of the MIM (ITO/ $\text{Al}_2\text{O}_3$ /Au) device. (b) The Current (I)-Voltage (V) curves of this MIM device, the low current density confirms the good insulation of both the ALD- $\text{Al}_2\text{O}_3$  and PLD- $\text{Al}_2\text{O}_3$  films.

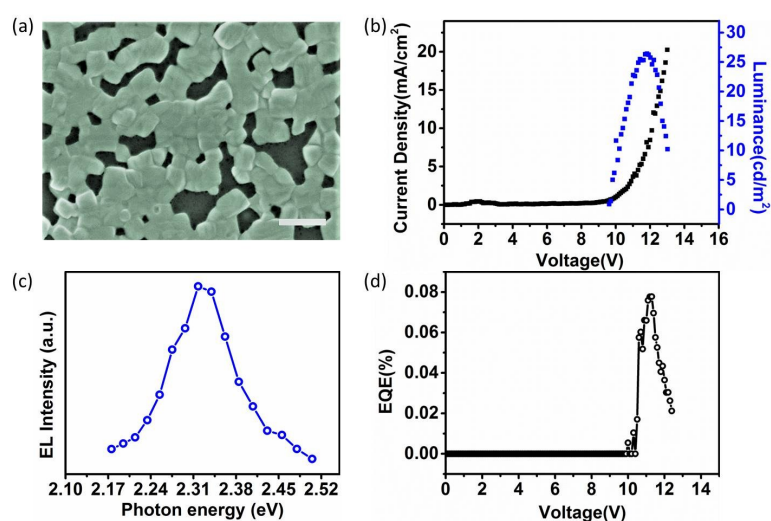


Figure S2. Fundamental characterization of perovskite-based MIS-LED device. (a) SEM image of  $\text{CH}_3\text{NH}_3\text{PbBr}_3$  perovskite thin film prepared on ALD- $\text{Al}_2\text{O}_3$  film, which contains some pinholes. Scale bar: 600 nm. (b) The current density (J)-voltage (V) and luminance (L)-voltage (V) curves of the MIS device, showing a turn-on bias voltage of  $\sim 9$ -10 V. (c) The electroluminescence spectra of the MIS device under a voltage bias of 11 V. (d) The external quantum efficiency (EQE)-voltage (V) curve of the best MIS device with the highest EQE  $\sim 0.077\%$ .